

# Advanced Techniques for Radiation Characterization of ProASIC3 FPGAs

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#### Outline



Background on ProASIC3 FPGAs

- SSI Heavy-Ion Micro Beam Facility
- RAMs and Flip-Flops







## **Background on ProASIC3 FPGAs**

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	A3PE3000L
Core Voltage (V)	1.2 1.5
Technology	130nm, 7ML
VeraTiles	75 264
4608 bit BRAMS	112
CCC (including PLL)	6
VersaNet Globals	18

#### CCC \_\_\_\_\_\_ RAM Block 4,608-Bit Dual-Port SRAM or FIFO Block Pro I/Os VersaTile RAM Block 4,608-Bit Dual-Port SRAM or FIFO Block ISP AES User Nonvolatile Flash\*Freeze Charo FlashRom Pumps Decryption\* Technology

One VersaTile can implement:

- Any 3 input combinatorial function
- A DFF or latch with options for  $\geq$ preset, clear, enable
- Configuration is controlled by floating gate switch







### SEE and Dose Extensively Studied



Radiation effects in ProASIC3 devices have been extensively studied !!

#### > New contributions :

- 1. Micro beam study showing sensitive regions
- 2. Image enhancement techniques for regular structures
- 3. In-depth study of effects on PLLs

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#### **Device Under Study : A3P3000L**



A3P3000L				
Number VersaTiles	75 264			
Number RAMs (4608 bits)	504			
Package	PQ208			
PLL / CCC	2/6			

Opened A3P3000L

Top-side opened by laser decapsulation, mechanical wet chemical finishing, coating removal, non-abrasive cleaner

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## **GSI Heavy Ion Micro Beam Facility**



### **GSI Micro Beam Facility**



Helmholtzzentrum f
ür Schwerionenforschung
 Located in Darmstadt (south of Frankfurt)



Vacuum Chamber



Temporal Beam Structure

- Ions are accelerated in linear accelerator (UNILAC) up to 11.4 MeV/µm
- ➢ Burst of ≈10 ions arrive every 200 msecs
- Tests performed with 2 ions : Au (94 MeVocm<sup>2</sup>/mg), Ti (19 MeVocm<sup>2</sup>/mg)
- ➢ Beam resolution is ≈500 nm (≈90% probability radius)

#### **Experimental Setup**



# 



- 1. Reset DUT
- 2. Open beam switch
- 3. Detect one ion
- 4. Close beam switch
- 5. Query DUT

- Individual ions targeted at specific locations on the die by X,Y magnets (12-bit resolution)
- > After each ion is fired, the response on the DUT must be queried
- Control card performs hand-shaking between facility and DUT



- Request an ion
- Wait for ion to be detected
- Record X,Y co-ordinates from facility
- Query whether error detected in DUT

- 432 µm x 432 µm
- Free running mode
  - Co-ordinates are "random"
  - Image progressively filled in



## **RAMs and Flip-Flops**



#### Test Sequence

- 1. Write pattern into memory. (~1.3 usec).
- 2. Read back pattern from memory + check. (~1.3 usec).
- 3. Wait for ions. (Handshaking).
- 4. Read back pattern from memory. (~1.3 usec). -> Report errors (macro, addr, bit)
- 5. Read back pattern from memory. (~1.3 usec). -> Report errors (macro, addr, bit)



#### **Imaging of BRAM (1)**



### Imaging of BRAM (2)





- Each colour dot represents an ion that produced a bit upset
- Colours assigned so each logical bit has unique colour
- Image is rotated versus optical image



#### **MCU** Patterns





MCU Patterns (Ti ions – 17 MeVcm<sup>2</sup>/mg) Many ions produced MCUs
 Exact patterns extracted
 No MBUs observed

 (>=2 bits in same word)

LET MeV∘cm2 /mg	Error %	SBU %	MCU2 %	MCU3 %	MCU4 %	MCU5 %	MCU6+ %
94 (Au)	79	52.6	16.8	5.13	3.58	0.6	0.23
17 (Ti)	35	29.2	5.1	0.66	0.02	0.02	0
Extent of MCUs (ratio versus number of ions fired)							



### **Imaging of Flip-Flops / Latches**



Au Ions (94 MeV°cm2 / mg)

	Local CS (cm²) Au ions 94 MeV°cm2 /mg	Local CS (cm²) Ti ions 19 MeV∘cm2 /mg
FF @ 0	9.03 e-6	2.58 e-6
FF @ 1	9.52 e-6	2.59 e-6
Latch @ 0	9.35 e-6	2.23 e-6
Latch @ 1	8.86 e-6	1.95 e-6

- Flip-flops, latches in arrays
- Sensitivity mapped storing 0,1
- Sensitive region is localized
- Local CS calculated as ratio of upsets to scanned area



Co-ordinates of each ion extracted to make a composite view for each logical bit position

Composite images superimposed to build amalgamated view

Increased spatial resolution of a single cell



## PLLs

### PLL Test Flow (On Chip Monitoring)

- Basic idea : sample CLK\_UUT at 8x
- At power-up, each sample point "locks" into position
- > 4 / 8 sample points "lock"
- ➢ Error if locked position moves (e.g. edge moves ≥ 25% cycle)



Clock Clock Clock Clock Clock Monitor 1 Monitor 2 Monitor 3 Monitor 4 Monitor 5 CLK 250 CLK UUT 1(62.5MHz PLL Under Test CLK\_UUT\_2(62.5MHz CLK 50 (in) REFERENCE GLB CLK\_UUT\_3(62.5MHz CLK 62.5 PLL YB VCO=125MHz CLK UUT 4(62.5MHz VCO=250MHz CLK 50 (out) GI C CLK UUT 5(62.5MHz

Reference PLL In : 50 MHz Out : 50,62.5,250 MHz PLL Under Test In : 50 MHz Output : 5 x (62.5 MHz)

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### PLL Test Flow (Off Chip Monitoring)



- To gain better insight into what is occurring when the PLL "error detector" triggers
- External DSO samples 4 of 5 of the PLL outputs
- Record signal trace if on-chip circuit triggers a PLL error

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### **PLL Sensitivity Map**



Events classified based on
 Did 1-4 or all 5 detectors fire?

Did loss of lock fire?

Very few of the real upsets triggered loss of lock (LoL). Can not use LoL for error detection....

PLL Sensitivity Map - 144 μm x 228 μm (Au Ions 94 MeV ° cm²/mg) light purple = 5 phase detectors triggered pink = 1-4 phase detectors triggered dark blue = loss of lock only yellow = phase detector and loss of lock



#### **Detailed PLL Effects**





#### **Missing Pulses**



#### Narrow/Wide Pulses



#### **Truncated Pulses**

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2.5

2

Voltage (V)

0.5

0

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#### **Temporary Frequency Shift**





### Conclusions



#### Conclusions

> HI micro-beam useful for identifying sensitive regions

- Increased experimental complexity
- > Makes sense early in process/circuit development
- Potential to provide detailed insight
   For circuit designers SEE weak spots
   For soft-error simulation detailed mapping
- Combining on-chip (detection) and off-chip (capture) techniques for detailed PLL effects analyis
- > PLL loss of lock can't be used for error detection in ProASIC3



## Thank You!

#### **Contacts**



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